

Dynamic Characteristics and Linewidth Enhancement Factor of Quantum-Dot Vertical-Cavity Surface-Emitting Lasers

Peng-Chun Peng, Gray Lin, Hao-Chung Kuo, *Senior Member, IEEE*, Chao-En Yeh, Jui-Nung Liu, Chun-Ting Lin, Jason (Jyehong) Chen, Sien Chi, Jim Y. Chi, *Senior Member, IEEE*, and Shing-Chung Wang, *Life Member, IEEE*

Abstract—This study explores the relative intensity noise characteristics of quantum-dot vertical-cavity surface-emitting lasers (QD VCSELs). The resonance frequency and eye diagram are presented. The linewidth enhancement factor (α factor) of QD VCSEL is also investigated experimentally. The values of α factor were measured to be between 0.48 and 0.60. Moreover, a photonic RF phase shifter is examined using the QD VCSEL. A phase shifter with a total phase shift of 2π was demonstrated. These investigations and demonstrations will be useful in the field of QD VCSEL.

Index Terms—Linewidth enhancement factor, quantum dot (QD), relative intensity noise (RIN), vertical-cavity surface-emitting laser (VCSEL).

I. INTRODUCTION

VERTICAL-CAVITY surface-emitting lasers (VCSELs) are highly promising for optical communication applications. Among the merits of VCSELs include their circular output beam, low power consumption, and low manufacturing cost. VCSELs fabricated on GaAs substrates have been expected to be high-performance and cost-effective light sources [1], [2]. Semiconductor lasers whose active regions contain quantum dots (QDs) have been demonstrated to have excellent characteristics, such as low threshold currents, low chirp, high differential gain, and insensitivity to temperature [3], [4]. QDs can be used to fabricate 0.98- μm GaAs-based VCSELs [5], [6]. However, the relative intensity noise (RIN) characteristics of QD VCSELs

have not been reported upon. The RIN peaks of a semiconductor laser are at the resonance frequencies of the small-signal modulation response of the laser [7]. The resonance frequency determines the modulation bandwidth of the semiconductor laser.

The linewidth enhancement factor, also known as the α factor, is an important parameter of semiconductor lasers. The α factor characterizes the chirp and linewidth broadening, which are detrimental to high-speed performance. The analysis of different material demonstrates that the α factor is generally smaller in quantum wells than in bulk, and it is even further reduced in strained materials, quantum wires, and QDs. Recently, the linewidth enhancement factor of quantum-well VCSEL with buried tunnel junction has been proposed [8]. The minimum value of linewidth enhancement factor is about 3.8 at low output power. Moreover, the linewidth enhancement factor of QD Fabry–Perot laser has also been reported. The linewidth enhancement factor of about 0.1 has been demonstrated [9]. Recently, significant progress has been made in the development of 1.3- μm QD VCSELs [10]. However, the linewidth enhancement factor of QD VCSEL has not yet been studied. In this paper, instead of measuring the below-threshold-amplified spontaneous emission spectra to determine the material differential refractive index versus differential gain as in conventional Hakki–Paoli method, the linewidth enhancement factor of 1.3- μm QD VCSEL was determined by the injection locking method [11].

Interest in the application of photonic technology to RF phase shifters for phased array antennas has been increasing recently. The advantage of the photonic RF phase shifter is its immunity to electromagnetic interference, excellent isolation, and its potential lightweight and small size [12]. Phase shifters and optical delay devices based on semiconductor lasers have become very attractive because of their inherent compactness, direct electrical controllability, and low power consumption [13], [14]. This paper presents a photonic RF phase shifter using the 1.3- μm QD VCSEL. A full 2π phase shift is achieved. The phase change is adjusted by controlling wavelength detuning ($\Delta\lambda = \lambda_{\text{probe}} - \lambda_{\text{VCSEL}}$), the difference between the wavelength of the probe signal and the lasing wavelength of QD VCSEL. The QD VCSEL can reduce the size and cost of an RF phase shifter used in microwave photonic systems.

The rest of this paper is organized as follows. Section II investigates the 0.98- μm QD VCSEL. Section III explores the linewidth enhancement factor of 1.3- μm QD VCSEL. Section IV examines the photonic RF phase shifter that is

Manuscript received October 31, 2008; revised December 1, 2008. Current version published June 5, 2009. This work was supported by the National Science Council of the Republic of China, Taiwan, under Contract NSC 97-2221-E-027-114 and Contract NSC 96-2628-E-009-017-MY3.

P. C. Peng is with the Department of Electro-Optical Engineering, National Taipei University of Technology, Taipei 106, Taiwan (e-mail: pepeng@ntut.edu.tw).

G. Lin is with the Department of Electronics Engineering, National Chiao Tung University, Hsinchu 300, Taiwan (e-mail: graylin@mail.nctu.edu.tw).

H.-C. Kuo, C.-E. Yeh, J.-N. Liu, C.-T. Lin, J. Chen, and S.-C. Wang are with the Department of Photonics and Institute of Electro-Optical Engineering, National Chiao Tung University, Hsinchu 300, Taiwan (e-mail: hckuo@faculty.nctu.edu.tw; yage0105@hotmail.com; l.y.n.@yahoo.com.tw; jinting@ms94.url.com.tw; jchen@mail.nctu.edu.tw; scwang@mail.nctu.edu.tw).

S. Chi is with the Department of Electro-Optical Engineering, Yuan Ze University, Chung Li 320, Taiwan (e-mail: schi@mail.nctu.edu.tw).

J. Y. Chi is with the Institute of Opto-Electronic Engineering, National Dong Hwa University, Hualien 974, Taiwan, and also with the Electronics and Optoelectronics Research Laboratories, Industrial Technology Research Institute, Hsinchu 310, Taiwan (e-mail: chij@itri.org.tw).

Color versions of one or more of the figures in this paper are available online at <http://ieeexplore.ieee.org>.

Digital Object Identifier 10.1109/JSTQE.2008.2011375

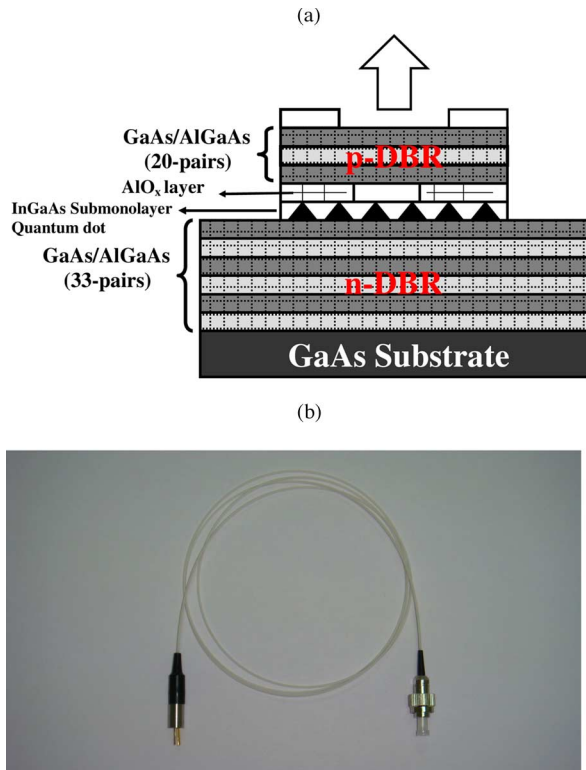


Fig. 1. (a) Schematic diagram of InGaAs submonolayer QD VCSEL. (b) TO-Can packaged QD VCSEL.

based on 1.3- μm QD VCSEL. Finally, Section V summarizes the research results.

II. 0.98- μm QD VCSEL

Fig. 1(a) schematically depicts the 0.98- μm QD VCSEL. The structure is grown on an n^+ -GaAs (1 0 0) substrate by molecular beam epitaxy (MBE). The bottom distributed Bragg reflector (DBR) comprises a 33-pair n-doped GaAs- $\text{Al}_{0.9}\text{Ga}_{0.1}\text{As}$. The undoped 1λ cavity contains three InGaAs submonolayer QD layers, separated by GaAs barrier layers. Each of the InGaAs QD layers is formed by the alternate deposition of InAs and GaAs. The top DBR has a 20-pair p-doped GaAs- $\text{Al}_{0.9}\text{Ga}_{0.1}\text{As}$. The structure of the device, including the thicknesses and compositions of the layers, are designed for a resonance wavelength of 0.98 μm . The wafer is processed to form a VCSEL structure. The fabrication method has been described elsewhere [5]. The submonolayer QD VCSEL is hermetically sealed using a standard transistor outline (TO)-Can laser package with a built-in lens. The QD VCSEL TO-Can package and the single-mode fiber are assembled by laser welding, as displayed in Fig. 1(b). Modulation experiments on our present QD VCSEL are performed at 2.5 and 3.2 Gb/s with a nonreturn-to-zero pseudorandom binary sequence (pattern length $2^{31} - 1$). The eye diagrams are wide open over a wide range of temperatures (-45°C – 20°C), as displayed in Fig. 2. The extinction ratios are over 11 dB. Fig. 3 presents the RIN spectra. The RIN spectra are measured at various bias currents using an electrical spectrum analyzer. The

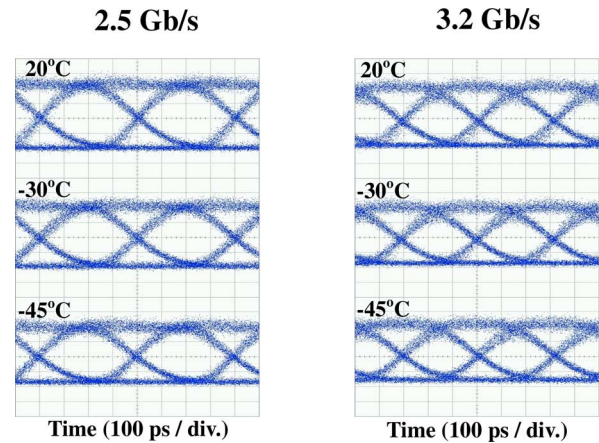


Fig. 2. Eye diagrams under 2.5- and 3.2-Gb/s modulation (20°C , -30°C , and -45°C).

inset in Fig. 3 plots the relationship between resonance frequency and driving current of the QD VCSEL. The maximum resonance frequency of the QD VCSEL is 5.85 GHz.

In this paper, we study the RIN peaks and eye diagram of 0.98- μm QD VCSEL at a wide range of temperatures (-45°C – 20°C). The RIN peaks are the resonance frequencies of 0.98- μm QD VCSEL. The resonance frequency is approximated proportional to the square root of the injected current relative to threshold before saturation takes place. The previous investigation [15] revealed the lasing emissions of QD VCSELs via the ground-state transition at low temperature, while via the excited state transition at room temperature. At the lowest ambient temperature of -45°C , the resonance frequency was observed to increase without saturation. The ground state lasing emission may contribute to the reduced damping in relaxation at low temperature under high current injection and is more resistant to the thermal effect as compared to that from excited state transition.

The frequency response of 1.3- μm QD VCSEL has been reported [10]. The RIN peaks of 1.3- μm QD VCSEL are around 1–2 GHz. The resonance frequency determines the intrinsic modulation bandwidth of QD VCSEL. The maximum modulation bandwidth for communication systems depends on the total frequency response of 0.98- μm TO-Can packaged QD VCSEL, including the intrinsic response of QD VCSEL (determined by the resonance frequency) and the response of laser package (determined by the TO-Can package). The maximum resonance frequency of the 0.98- μm QD VCSEL is 5.85 GHz. Therefore, the 0.98- μm QD VCSEL with high-speed package could be used for the over 5.85 Gb/s communication systems.

III. LINEWIDTH ENHANCEMENT FACTOR OF 1.3- μm QD VCSEL

The linewidth enhancement factor is measured using an injection locking approach [11]. Fig. 4 schematically depicts the InAs/InGaAs QD VCSEL. A QD VCSEL structure was grown on a GaAs substrate by MBE. The epitaxial structure was as follows (from bottom to top)— n^+ -GaAs buffer, 33.5-pair n^+ - $\text{Al}_{0.9}\text{Ga}_{0.1}\text{As}/n^+$ -GaAs (Si-doped) DBR,

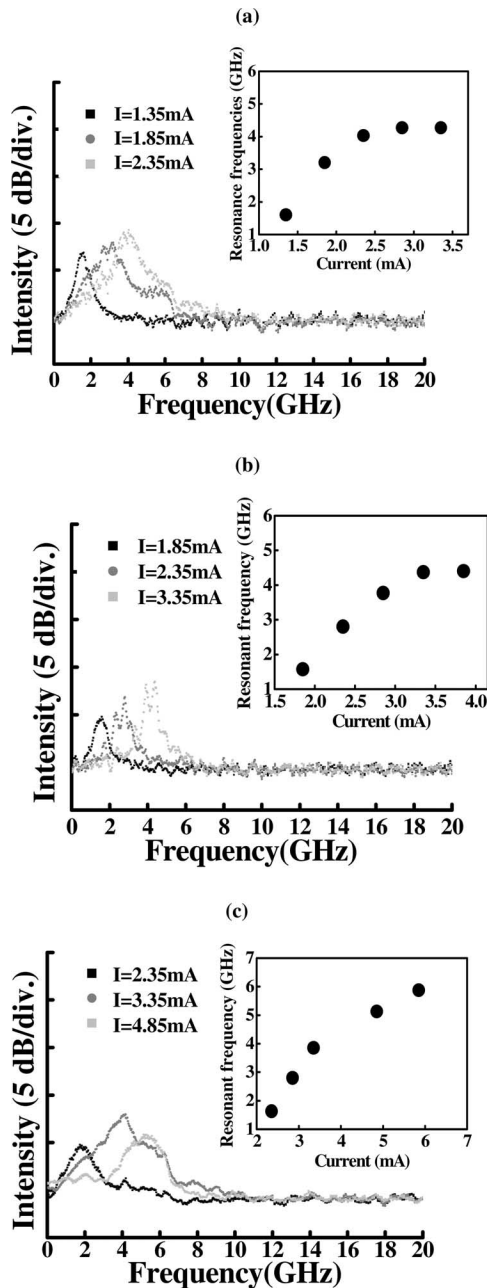


Fig. 3. RIN spectra at (a) 20 °C, (b) -30 °C, and (c) -45 °C.

undoped active region, p-Al_{0.98}Ga_{0.02}As oxidation layer, 22-pair p⁺-Al_{0.9}Ga_{0.1}As/p⁺-GaAs DBR (carbon-doped), and p⁺-GaAs (carbon-doped) contact layer. The graded-index separate confinement heterostructure (GRIN-SCH) active region primarily comprised five groups of QDs active region, embedded between two linearly graded Al_xGa_{1-x}As ($x = 0-0.9$ and $x = 0.9-0$) confinement layers. The thickness of the cavity active region was 3λ . Each group of QDs comprised three QD layers around the antinode of a standing wave. The wafer was then processed into a VCSEL structure.

Fig. 5 presents the light-current characteristics of the QD VCSEL. The threshold current is approximately 1.1 mA ($I_{th} = 1.1$ mA). The QD VCSEL is hermetically sealed using a TO-Can

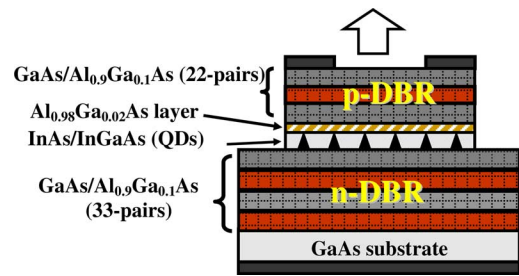


Fig. 4. Schematic diagram of InAs/InGaAs QD VCSEL.

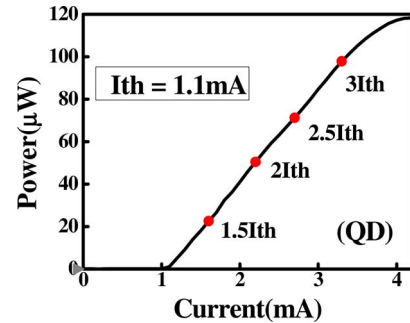


Fig. 5. Light-current characteristics of QD VCSEL.

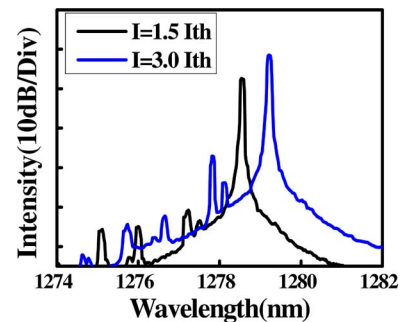


Fig. 6. Output spectrum of QD VCSEL.

package. The TO-Can packaged QD VCSEL and the single-mode fiber are assembled by laser welding. Fig. 6 displays the output spectrum of the QD VCSEL. The lasing wavelength of the QD VCSEL is around 1279 nm at room temperature. The spiky spectrum to the left of the peak wavelength shows lasing in multiple transverse modes, which is the case for index-guided oxide-confined VCSELs without optimized oxide aperture [16]. Selective modal loss by surface-relief technique or implantation before oxidation was reported to achieve fundamental-mode operation with high side-mode suppression ratio (SMSR). Fig. 7 displays the experimental setup for measuring the linewidth enhancement factor. The VCSEL is employed as the slave laser, and a 1.3- μ m tunable laser is used as the master laser. The optical power is varied using a variable optical attenuator (VA) at the output of the tunable laser. Fig. 10 plots the relationship between the driving current of QD VCSEL and the linewidth enhancement factor. The linewidth enhancement factor of QD VCSEL is varied from 0.48 to 0.60. Fig. 8 plots the light-current characteristics of a commercial quantum well (QW) VCSEL (InAlGaAs/InP QWs). The threshold current is about

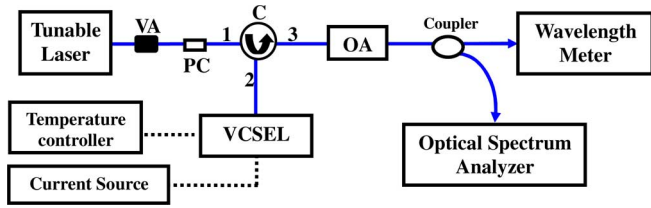


Fig. 7. Experimental setup for measuring the linewidth enhancement factor (VA: variable optical attenuator; PC: polarization controller; C: optical circulator; OA: optical amplifier).

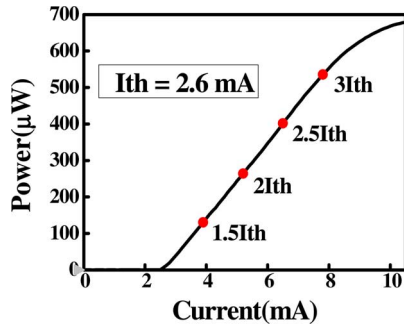


Fig. 8. Light-current characteristics of QW VCSEL.

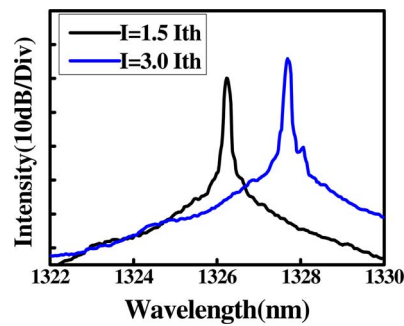


Fig. 9. Output spectrum of QW VCSEL.

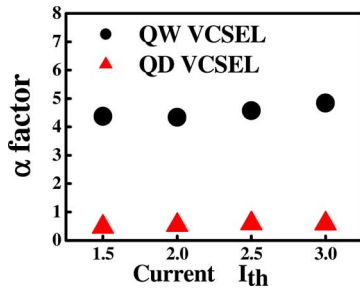


Fig. 10. Relationship between the driving current of VCSEL and the linewidth enhancement factor.

2.6 mA ($I_{th} = 2.6$ mA). Fig. 9 displays the output spectrum of the QW VCSEL. The lasing wavelength of the QW VCSEL is about 1327 nm at room temperature. Fig. 10 plots the linewidth enhancement factor at various driving currents of the QW VCSEL. The linewidth enhancement factor of the QW VCSEL varies from 4.34 to 4.84 with the driving current of the QW VCSEL.

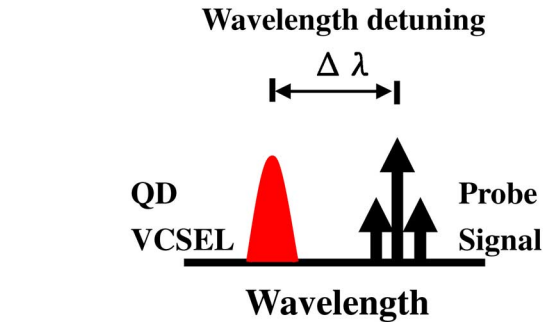
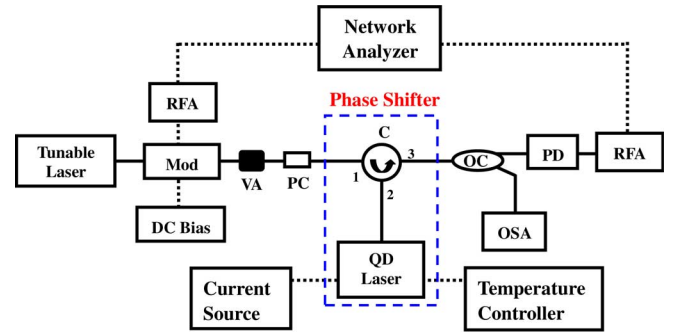


Fig. 11. Experimental setup for measuring the RF phase shift in the QD VCSEL (Mod: electrooptical modulator; PC: polarization controller; VA: variable optical attenuator; C: optical circulator; OC: optical coupler; OSA: optical spectrum analyzer; RFA: RF amplifier; PD: photodetector).

IV. RF PHASE SHIFTER USING 1.3- μ m QD VCSEL

Fig. 11 presents the experimental setup for measuring the RF phase shift in the QD VCSEL. A probe signal is generated using a tunable laser and then modulated using an electrooptical modulator. The electrooptical modulator is modulated using a network analyzer. The signal power is controlled using a VA at the output of the electrooptical modulator. The polarization of the probe signal is adjusted using a polarization controller. The probe signal is coupled into the QD VCSEL by using an optical circulator. Next, the output signal from port 3 of the circulator is split into two paths, which are sent to an optical spectrum analyzer and a photodetector, respectively. Finally, the amplitude and phase changes are measured using the network analyzer.

In the experiment, the power of the input probe signal is held constant as the wavelength of probe signal is varied. The power of the probe signal is -14 dBm, and the QD VCSEL is biased at $2.125 I_{th}$. Varying the power of the probe signal in the cavity of QD VCSEL will vary the available gain. The amplitude and phase change response indicates the locked amplitude and phase change, calibrated with reference to the unlocked values. Fig. 12 plots the amplitude and phase change response of the QD VCSEL at various wavelength detunings. Increasing wavelength detuning increases the frequency of the phase shift. A phase change of 2π is observed. The phase change can be tuned by adjusting wavelength detuning $\Delta\lambda$.

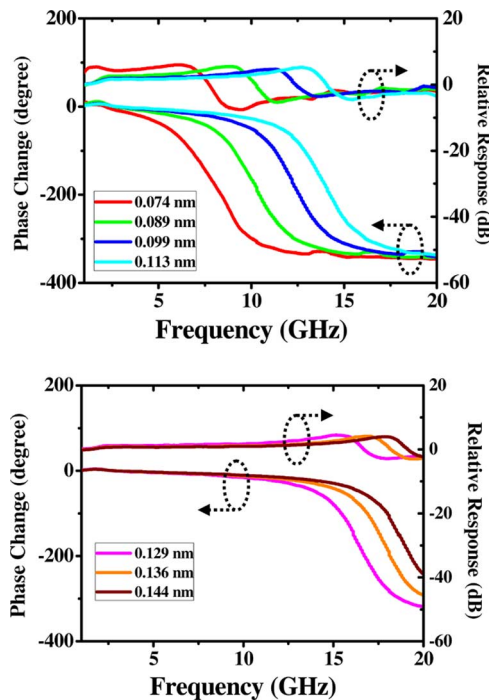


Fig. 12. Amplitude and phase change response of the QD VCSEL at various wavelength detunings.

V. CONCLUSION

This study describes the RIN characteristics of a QD VCSEL. The intrinsic resonance frequency and eye diagram of the QD VCSEL are presented. The linewidth enhancement factor of the QD VCSEL is also investigated. The α factor was measured to be 0.48–0.60. The linewidth enhancement factor of commercial QW VCSEL was also examined. A photonic RF phase shifter that is based on the QD VCSEL was demonstrated. A photonic RF phase shifter with a total phase shift of 2π was demonstrated. The relationship between the amplitude change response and the wavelength detuning was examined. The QD VCSEL has the potential to reduce the size and cost of the RF phase shifters used in a phased array antenna. Results of this study are useful in the field of QD VCSEL.

ACKNOWLEDGMENT

The authors would like to thank Dr. A. R. Kovsh of NL Nanosemiconductor GmbH, Germany, and Dr. N. A. Maleev of the Ioffe Physico-Technical Institute, Russia, for providing the epitaxial wafers.

REFERENCES

- [1] H. C. Kuo, Y. H. Chang, Y. A. Chang, F. I. Lai, J. T. Chu, M. N. Tsai, and S. C. Wang, "Single-mode $1.27\ \mu\text{m}$ InGaAs:Sb–GaAs–GaAsP quantum well vertical cavity surface emitting lasers," *IEEE J. Sel. Topics Quantum Electron.*, vol. 11, no. 1, pp. 121–126, Jan./Feb. 2005.
- [2] Y. H. Chang, H. C. Kuo, F. I. Lai, Y. A. Chang, C. Y. Lu, L. H. Lai, and S. C. Wang, "Fabrication and characteristics of high-speed oxide-confined VCSELs using InGaAsP–InGaP strain-compensated MQWs," *J. Lightw. Technol.*, vol. 22, pp. 2828–2833, 2004.

- [3] N. N. Ledentsov, "Long-wavelength quantum-dot lasers on GaAs substrates: From media to device concepts," *IEEE J. Sel. Topics Quantum Electron.*, vol. 8, no. 5, pp. 1015–1024, Sep./Oct. 2002.
- [4] V. M. Ustinov, N. A. Maleev, A. R. Kovsh, and A. E. Zhukov, "Quantum dot VCSELs," *Phys. Status Solidi A*, vol. 202, pp. 396–402, 2005.
- [5] F. I. Lai, H. P. D. Yang, G. Lin, I. C. Hsu, J. N. Liu, N. A. Maleev, S. A. Blokhin, H. C. Kuo, and J. Y. Chi, "High-power single-mode submonolayer quantum-dot photonic crystal vertical-cavity surface-emitting lasers," *IEEE J. Sel. Topics Quantum Electron.*, vol. 13, no. 5, pp. 1318–1323, Sep./Oct. 2007.
- [6] S. A. Blokhin, N. A. Maleev, A. G. Kuzmenkov, A. V. Sakharov, M. M. Kulagina, Y. M. Shernyakov, I. I. Novikov, M. V. Maximov, V. M. Ustinov, A. R. Kovsh, S. S. Mikhlin, N. N. Ledentsov, G. Lin, and J. Y. Chi, "Vertical-cavity surface-emitting lasers based on submonolayer InGaAs quantum dots," *IEEE J. Quantum Electron.*, vol. 42, no. 9, pp. 851–858, Sep. 2006.
- [7] X. Jin and S. L. Chuang, "Relative intensity noise characteristics of injection-locked semiconductor lasers," *Appl. Phys. Lett.*, vol. 77, no. 9, pp. 1250–1252, 2000.
- [8] H. Halbritter, R. Shau, F. Riemenschneider, B. Kogel, M. Ortsiefer, J. Roskopf, G. Bohm, M. Maute, M. C. Amann, and P. Meissner, "Chirp and linewidth enhancement factor of $1.55\ \mu\text{m}$ VCSEL with buried tunnel junction," *Electron. Lett.*, vol. 40, pp. 1266–1268, 2004.
- [9] T. C. Newell, D. J. Bossert, A. Stintz, B. Fuchs, K. J. Malloy, and L. F. Lester, "Gain and linewidth enhancement factor in InAs quantum-dot laser," *IEEE Photon. Technol. Lett.*, vol. 11, no. 12, pp. 1527–1529, Dec. 1999.
- [10] P. C. Peng, H. C. Kuo, W. K. Tsai, Y. H. Chang, G. Lin, C. T. Lin, H. P. Yang, K. F. Lin, H. C. Yu, J. Y. Chi, S. Chi, and S. C. Wang, "Dynamic characteristics of long-wavelength quantum dot vertical-cavity surface-emitting lasers with light injection," *Opt. Exp.*, vol. 14, pp. 2944–2949, 2006.
- [11] G. Liu, X. Jin, and S. L. Chuang, "Measurement of linewidth enhancement factor of semiconductor lasers using an injection-locking technique," *IEEE Photon. Technol. Lett.*, vol. 13, pp. 430–432, 2001.
- [12] E. H. W. Chan and R. A. Minasian, "Photonic RF phase shifter and tunable photonic RF notch filter," *J. Lightw. Technol.*, vol. 24, pp. 2676–2682, 2006.
- [13] M. R. Fisher and S. L. Chuang, "A microwave photonic phase-shifter based on wavelength conversion in a DFB laser," *IEEE Photon. Technol. Lett.*, vol. 18, no. 16, pp. 1714–1716, Aug. 2006.
- [14] X. Zhao, Y. Zhou, C. J. Chang-Hasnain, W. Hofmann, and M. C. Amann, "Novel modulated-master injection-locked $1.55\text{-}\mu\text{m}$ VCSELs," *Opt. Exp.*, vol. 14, pp. 10500–10507, 2006.
- [15] S. A. Blokhin, A. V. Sakharov, N. A. Maleev, M. M. Kulagina, Y. M. Shernyakov, I. I. Novikov, N. Y. Gordeev, M. V. Maximov, A. G. Kuzmenkov, V. M. Ustinov, N. N. Ledentsov, A. R. Kovsh, S. S. Mikhlin, G. Lin, and J. Y. Chi, "The impact of thermal effects on the performance of vertical-cavity surface-emitting lasers based on sub-monolayer InGaAs quantum dots," *Semicond. Sci. Technol.*, vol. 22, pp. 203–208, 2007.
- [16] E. W. Young, K. D. Choquette, S. L. Chuang, K. M. Geib, A. J. Fischer, and A. A. Allerman, "Single-transverse-mode vertical-cavity lasers under continuous and pulsed operation," *IEEE Photon. Technol. Lett.*, vol. 13, no. 9, pp. 927–929, Sep. 2001.

Peng-Chun Peng received the Ph.D. degree from the Institute of Electro-Optical Engineering, National Chiao Tung University, Hsinchu, Taiwan, in 2005.

From 2006 to 2008, he was an Assistant Professor in the Department of Applied Materials and Optoelectronic Engineering, and the Department of Electrical Engineering, National Chi Nan University, Taiwan. In 2008, he joined the Department of Electro-Optical Engineering, National Taipei University of Technology, Taipei, Taiwan, as an Assistant Professor. His current research interests include optical communication systems, vertical-cavity surface-emitting lasers, fiber sensors, optical signal processing, and microwave photonics.

Gray Lin received the B.S., M.S., and Ph.D. degrees from the Department of Electronics Engineering and Institute of Electronics, National Chiao-Tung University, Hsinchu, Taiwan, R.O.C., in 1994, 1995, and 2001, respectively.

From 2001 to 2007, he worked at the Opto-Electronics and Systems Laboratories, Industrial Technology Research Institute, Hsinchu, Taiwan. Since February 2007, he joined the National Chiao-Tung University as a Faculty Member of Department of Electronics Engineering. His research interests include molecular beam epitaxy (MBE) growth of GaAs-based compound semiconductor materials, design, and fabrication of semiconductor lasers, both edge-emitting and surface-emitting, as well as characterization and analysis of optoelectronic devices.

Hao-Chung Kuo (M'98–SM'06) received the B.S. degree in physics from the National Taiwan University, Taipei, Taiwan, the M.S. degree in electrical and computer engineering from Rutgers University, New Brunswick, NJ, in 1995, and the Ph.D. degree from the Electrical and Computer Engineering Department, University of Illinois at Urbana Champaign, Champaign, in 1999.

He has an extensive professional career both in research and industrial research institutions. He was a Research Consultant at Lucent Technologies, Bell Laboratories (1993–1995); a Senior Research Engineer at Filtronic Solid State (1999–2000); and a Member of the Technical Staff, Fiber-Optics Division, Agilent Technologies (2000–2001) and LuxNet Corporation (2001–2002). Since October 2002, he has been a Faculty Member of the Institute of Electro-Optical Engineering, National Chiao Tung University, Hsinchu, Taiwan. His current research interests include semiconductor lasers, vertical-cavity surface-emitting laser (VCSELs), blue and UV LED lasers, quantum-confined optoelectronic structures, optoelectronic materials, and high-speed semiconductor devices. He is the author or coauthor of more than 80 internal journal papers and four granted patents.

Dr. Kuo is a member of the International Society for Optical Engineering (SPIE) and the Materials Research Society (MRS).

Chao-En Yeh received the B.S. degree in electrical engineering from the National Chung Cheng University, Minsyong, Taiwan, in 2006, and the M.S. degree from the Department of Photonics, National Chiao Tung University, Hsinchu, Taiwan, in 2008.

He is currently with the National Chiao Tung University. His current research interests include vertical-cavity surface-emitting lasers and dynamic characteristics of semiconductor lasers.

Jui-Nung Liu, photograph and biography not available at the time of publication.

Chun-Ting Lin received the B.S. and M.S. degrees in material science and engineering from the National Tsing Huang University, Hsinchu, Taiwan, in 1997 and 2001, respectively, and the Ph.D. degree in electrooptical engineering from the National Chiao-Tung University, Hsinchu, in 2007.

He is currently with the Department of Photonics and the Institute of Electro-Optical Engineering, National Chiao-Tung University. His current research interests include radio-over-fiber systems, optical data formats, and optoelectronic packages.

Jason (Jyehong) Chen received the B.S. and M.S. degrees in electrical engineering from the National Taiwan University, Taipei, Taiwan, R.O.C., in 1988 and 1990, respectively, and the Ph.D. degree in electrical engineering and computer science from the University of Maryland, Baltimore, in 1998.

He joined JDS Uniphase Inc., in 1998 as a Senior Engineer and obtained ten U.S. patents in two years. He joined the faculty of National Chiao-Tung University, Hsinchu, Taiwan, in 2003, where he is currently an Associate Professor in the Institute of Electro-Optical Engineering and Department of Photonics.

Sien Chi received the B.S.E.E. degree from the National Taiwan University, Taipei, Taiwan, in 1959, the M.S.E.E. degree from the National Chiao-Tung University, Hsinchu, Taiwan, in 1961, and the Ph.D. degree in electrophysics from the Polytechnic Institute, Brooklyn, NY, in 1971.

From 1971 to 2004, he was a Professor at the National Chiao-Tung University, where he was the Vice President from 1998 to 2001. He is currently a Chair Professor at Yuan-Ze University, Chung Li, Taiwan. His current research interests include optical-fiber communications, optical solitons, optical modulation format, and optical-fiber amplifiers.

Prof. Chi is a Fellow of the Optical Society of America (OSA).

Jim Y. Chi (SM'97) received the B.S. degree in physics from the National Tsinghua University, Hsinchu, Taiwan, R.O.C., in 1971 and the Sc.D. degree in material science from the Massachusetts Institute of Technology, Cambridge, in 1979.

He is currently the Director of the Institute of Opto-Electronic Engineering and the Institute of Electronics Engineering, National Dong Hwa University, Hualien, Taiwan. He has been working at the Industrial Technology Research Institute (ITRI), Hsinchu, as a Director and Projector Leader for advanced light sources for the next generation of optoelectronics systems including the long-wavelength vertical-cavity surface-emitting laser (VCSEL) and LDs using InGaAs materials, GaN blue, and green lasers, and 980-nm high-power lasers for optical amplifier applications. He has authored and coauthored more than 200 technical papers and conference papers, and has given many invited talks at conferences and institutions.

Dr. Chi won numerous awards for his technical achievements including the 2004 Distinguished Engineers Award by the Association of Chinese Engineers, Taiwan.

Shing-Chung Wang (M'79–SM'03–LM'07) received the B.S. degree from the National Taiwan University, Taipei, Taiwan, the M.S. degree from the National Tohoku University, Sendai, Japan, and the Ph.D. degree from Stanford University, Stanford, CA, in 1971, all in electrical engineering.

He has an extensive professional career both in academic and industrial research institutions. He was a faculty member at the National Chiao Tung University (1965–1967), a Research Associate at Stanford University (1971–1974), a Senior Research Scientist at Xerox Corporation (1974–1985), and a Consulting Scientist at Lockheed-Martin Palo Alto Research Laboratories (1985–1995). In 1995, he rejoined the National Chiao Tung University, Hsinchu, Taiwan, as a faculty member of the Institute of Electro-Optical Engineering.

Prof. Wang is a Fellow of the Optical Society of America. He was the recipient of the Outstanding Scholar Award from the Foundation for the Advancement of Outstanding Scholarship.